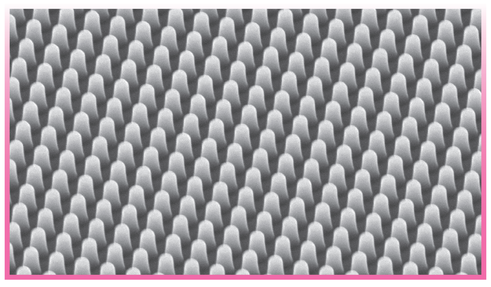
micro resist technology

Your Experts for Photoresists and Polymers

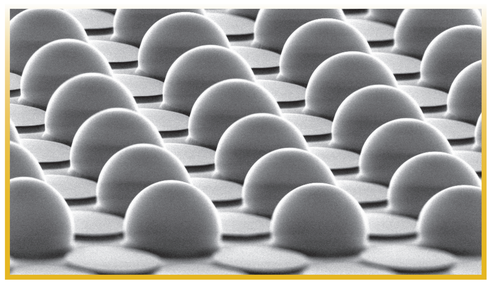
Materials and Technologies for Micro- and Nanofabrication

UV-Nanoimprint lithography



Etch mask
Micro/ nanofabrication
mr-NIL210
mr-NIL200
mr-UVCur26SF
mr-XNIL26SF
mr-NIL 6000E

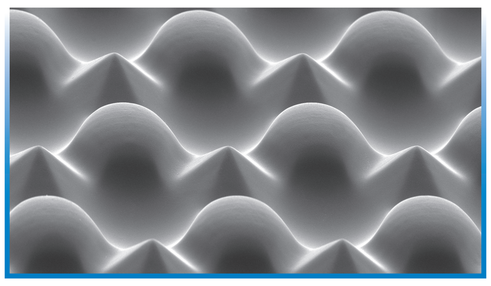
Micro optical components



UV replication/ imprint
Inkjet printing
Direct laser writing/ TPA

OrmoComp®
OrmoClear®FX
OrmoClear®
InkOrmo

Greyscale lithography



Master generation

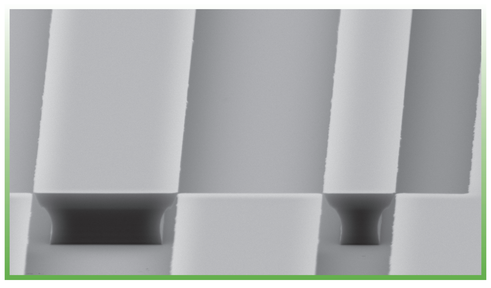
ma-P 1200G

E-Beam/ Deep UV lithography

Etch mask
Stamp/
template manufacture

ma-N 2400
mr-EBL 6000

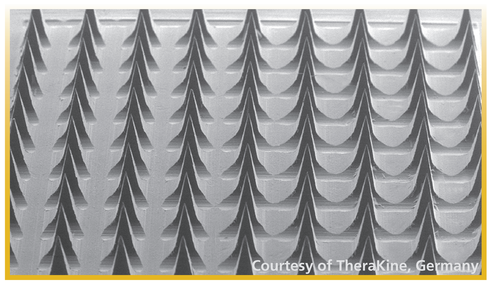
UV lithography



Lift-off process
Etch mask, Inkjet Printing
Mould for electroplating
SM & MM waveguides

ma-N 400 EpoCore InkEpo
ma-N 1400 EpoClad

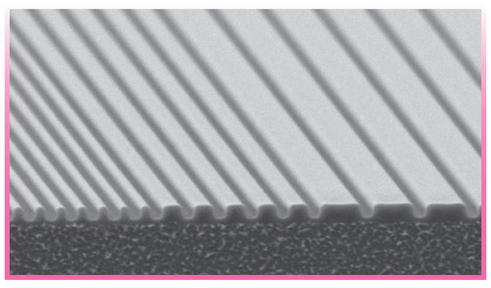
Bio applications/ Life Science



UV replication/ imprint
Direct laser writing/ TPA

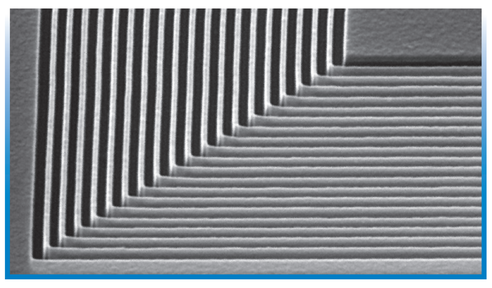
OrmoComp®
OrmoClear®FX

Thermal nanoimprint lithography



Etch mask
Micro/nanofabrication
mr-I 7000R
mr-I 8000R
mr-I 9000M
SIPOL
mr-I T85

E-Beam lithography



Etch mask
Template manufacture

mr-PosEBR

Product Lines

Negative Photoresists | Positive Photoresists | Hybrid Polymers | NIL Materials

OrmoComp®: DE 30 210 075 433; IR 1 091 982 ; TW 100030626; OrmoClear®: DE 30 210 075 434; IR 1 091 359 ; TW 100030628; OrmoStamp®: DE 30 210 075 435; IR 1 092 621 ; TW 100030629; OrmoPrime®: DE 30 210 075 436

www.microresist.com

© micro resist technology GmbH 2019

micro resist technology GmbH
Berlin - Germany